

**NOVEL ACRYL MONOMER, POLYMER AND RESIST COMPOSITION
COMPRISING SAME**

5

ABSTRACT

Disclosed are an acrylic monomer having a structure represented by formula (1),
a polymer containing a repeating unit derived from the acrylic monomer, and a resist
composition prepared by using the polymer, which exhibits excellent adhesiveness,
10 storage stability, and enhanced line width roughness, exhibits excellent resolution in both
C/H patterns and L/S patterns, has an excellent process window so that an excellent
pattern profile can be obtained regardless of the type of the substrate, and exhibits
improved contrast.

15 Figure 1